AMENDMENTS TO THE CLAIMS:

Please amend the claims as detailed herein.

1. (Currently Amended) A method of <u>high contrast</u> imaging <u>of</u> semiconductor <u>and metallic</u> sites in an integrated circuit (IC), <u>comprising the steps of</u>: setting up a device that simultaneously produces two separate <u>exclusive high-contrast</u> images of a <u>sample</u> of said IC from one light source; and refining said images to generate an exclusive high-contrast image of said semiconductor sites, the method comprising:

exciting said IC with a focused excitation beam from a light source;

transversely and axially scanning said IC by said focused excitation beam;

producing simultaneously a high-contrast confocal reflectance image $i_f(x, y, z)$ and a low contrast one-photon optical beam-induced current image (1P-OBIC) $i_s(x, y)$ of said IC;

deriving a first exclusive high-contrast image s(x, y, z) of said semiconductor sites of said IC from a pixel to pixel product of said 1P-OBIC image and said confocal reflectance image using the equation: $s(x, y, z) = i_f(x, y, z)i_s(x, y)$ where s(x, y, z) > 0; and

deriving a second exclusive high-contrast image m(x, y, z) of said metallic sites of said IC from a product of a complementary to said 1P-OBIC image and said confocal reflectance image using the equation: $m(x, y, z) = i_r(x, y, z)i_m(x, y)$ where $i_m(x, y) = \kappa - i_s(x, y)$ and κ is a constant that represents the highest s(x, y, z) value that is possible for a given optical set-up.

2-3. (Canceled)

- 4. (Currently amended) The method of claim 3claim 1, wherein said microscope said focused excitation beam is a beam-scanning confocal reflectance microscope that simultaneously generates both a one-photon optical beam-induced current (1P-OBIC) image and a confocal reflectance image of the IC sample.
- 5. (Currently amended) The method of-claim 3 claim 1, wherein said light source is selected from the group consisting of a laser and a spectrally filtered light source with a broadband spectrum.

6. (Cancelled)

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- 7. (Currently amended) The method of claim 5, wherein said device includes a scanning mirror system having two galvanometer mirrors for x and y scanning, and two lenses that constitute a 4f transfer lens, wherein said light source has an output beam that is directed to said scanning mirror system via a beam splitter.
- 8. (Currently amended) The method of claim 7, wherein said device includes another pair of lenses that expand and collimate said scanned output excitation beam and inputs said scanned output excitation beam to an optical microscope assembly.
- 9. (Currently amended) The method of claim 8, wherein said device includes an Infinity-corrected objective lens that focuses said <u>excitation</u> beam into <u>an exposed top surface of said integrated circuit</u> said IC.
- 10. (Currently amended) The method of claim 9, wherein said device includes a pair of digital-to-analog converters to achieve precise two-dimensional scan control of said focused excitation beam.
- 11. (Currently amended) The method of claim 10, wherein said device provides reflected light that is collected back by said Infinity-corrected objective lens and focused

by a lens towards a pinhole that is placed in front of-said_a photodetector.

12. (Previously presented) The method of claim 11, wherein said 1P-OBIC is measured by inputting an output of said pinhole that is nearest to a probe surface area to a current-to-voltage converter composed of an operational amplifier and a feedback resistor.

13. (Currently amended) The method of claim 12, wherein said device includes another converter input that is a common reference for electronic circuits including the integrated circuit sample said IC.

14-15. (Canceled)